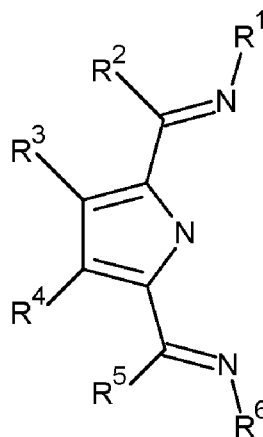




- (51) **International Patent Classification:**
C23C 16/455 (2006.01) C07F 3/00 (2006.01)
- (21) **International Application Number:**
PCT/EP2015/051181
- (22) **International Filing Date:**
22 January 2015 (22.01.2015)
- (25) **Filing Language:** English
- (26) **Publication Language:** English
- (30) **Priority Data:**
14152683.0 27 January 2014 (27.01.2014) EP
- (71) **Applicant:** BASF SE [DE/DE]; 67056 Ludwigshafen (DE).
- (72) **Inventors:** XU, Ke; Poststr. 32, 58452 Witten (DE). SCHILDKNECHT, Christian; Carl-Bosche-Str. 38, 67056 Ludwigshafen (DE). SPIELMANN, Jan; Rheintal-bahnstraße 2-4, 68199 Mannheim (DE). FRANK, Jürgen; Altholzweg 31, 67065 Ludwigshafen (DE). BLASBERG, Florian; Rotlintstr. 120, 60389 Frankfurt (DE). GÄRTNER, Martin; Dreihornmühlgasse 36b, 67549 Worms (DE). LÖFFLER, Daniel; Heinrich Heine Str. 2b, 67134 Birkenheide (DE). WEIGUNY, Sabine; Dr. Kausch Str. 4a, 67251 Freinsheim (DE). SCHIERLE-ARNDT, Kerstin; Stuckertstr. 23a, 64673 Zwingenberg (DE).
- (74) **Common Representative:** BASF SE; 67056 Ludwigshafen (DE).
- (81) **Designated States** (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IR, IS, JP, KE, KG, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.
- (84) **Designated States** (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, ST, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).
- Published:**
— with international search report (Art. 21(3))

(54) **Title:** PROCESS FOR THE GENERATION OF THIN INORGANIC FILMS



(57) **Abstract:** The present invention relates to a process for the generation of thin inorganic films on substrates, in particular an atomic layer deposition process. This process comprises bringing a compound of general formula (I) into the gaseous or aerosol state and depositing the compound of general formula (I) from the gaseous or aerosol state onto a solid substrate, wherein R^1 , R^2 , R^3 , R^4 , R^5 , and R^6 are independent of each other hydrogen, an alkyl group, or a trialkylsilyl group, n is an integer from 1 to 3, M is a metal or semimetal, $1 \leq X$ is a ligand which coordinates M , and m is an integer from 0 to 4.

